

# LAM Research 4528i Oxide Etch 200mm Configuration SN 24041

## LAM Research 4520i Oxide Etch SN 24041







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### LAM Research 4528i Oxide Etch SN 24041



Tool Model: 4528i Single lower chamber endpoint detector (405/520nm) Non-

Tool Serial Number: 24041 -heated endpoint window

Bulkhead system mount w/tunnel covers

Hine 38A open cassette Send/Receive indexers

Software Version: Envision 1.5.2

Low pressure chamber manifold

HPS valve for chamber isolation

AC--2 chamber pressure control

Oxide etcher, 8"

Clamp type, ESC

Lower chamber RGA port
8 -- Gas box Orbital gas box

RF power Rack ENI Paramount 1213 Paramount MF 3KW Gas 1: AR 500 sccm

AE Isotropic Module Gas 2: CF4 200 sccm Chiller Unit (LAM 2080) Gas 3: CHF3 100 sccm

AC Rack AC Power Distribution Gas 4: SF6 100 sccm

Moving gap

Back Helium Colling

Main Power 208V, 3 Phase, 5Wire, 175A, 60/

Gas 5: N2 100 sccm

Gas 6: H2 1000 sccm

Gas 7 NF3 1000 sccm

Belt driven load station Gas 1-: O2 100sccm
Standard load station shuttle spatula UPC: He (50 sccm)

Upper chamber gap drive encoder

AC input box for AC power inlet

AC input box for AC power hove

Dip PCB for RF power tuning

Trip breakers AC/DC power box

Aluminum upper chamber electrode

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